

Notice of References Cited	Application/Control No. 10/606,854		Applicant(s)/Patent Under Reexamination HARTLOVE ET AL.	
	Examiner Tuan N Nguyen		Art Unit 2828	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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NON-PATENT DOCUMENTS

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*	U	Prepulse enhanced EUV yield from a xenon gasjet laser produced plasma□□G Kooijman, R de Bruijny K Kosllelev*, F Bijkerk, Lasers for Science Facility Programme - Physics, Central Laser Facility Annual Report 2001/2002,□□p.142-144.				
*	V	Ultraviolet prepulse for enhanced x-ray emission and brightness from droplet-target laser plasmas□□M. Berglund,a) L. Rymell, and H. M. Hertz, Appl. Phys. Lett, Vol. 69, N. 12, 16 September 1996, p1683-1685.				
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.